

----- **GENERAL INFORMATION** -----

DATA TITLE: SEM/EDS analysis of surfaces of ferritic Fe-Cr-Al-Mo alloy Kanthal APMT and Cr-Mo-V steel T91 (UNS: K90901) after oxidation at 1200 C for 2 h

PROJECT TITLE: Materials Characterization of High-Temperature Oxidation on ferritic Fe-Cr-Al-Mo alloy Kanthal APMT and Cr-Mo-V steel T91 (UNS: K90901)

DATA ABSTRACT: Scanning electron microscopy (SEM) secondary electron images of surfaces on ferritic Fe-Cr-Al-Mo alloy Kanthal APMT and Cr-Mo-V steel T91 (UNS: K90901) before and after oxidation at 1200 degrees Celsius for 2 h in steam or air. Metadata detailing SEM imaging settings are included for each photo.

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**ASSOCIATED PUBLICATIONS:**

T. Copeland-Johnson, C.K.A. Nyamekye, S.K. Gill, L. Ecker, N. Bowler, E.A. Smith, R.B. Rebak, Characterization of Kanthal APMT and T91 oxidation at beyond design-basis accident temperatures, Corros. Sci. (2020).

**COLLECTION INFORMATION:**

Time period(s): 2017-2019

Location(s): Iowa State University, Brookhaven National Laboratory

**----- FILE DIRECTORY -----**

**----- FILE LIST-----**

File Name	Description
SEM_APMT_Air.jpg	Secondary electron image of the surface of Kanthal APMT after oxidation in air.
SEM_APMT_Air_Metadata.txt	Metadata for secondary electron image of the surface of Kanthal APMT after oxidation in air.
SEM_APMT_Control.jpg	Secondary electron image of the surface of Kanthal APMT before oxidation.
SEM_APMT_Control_Metadata.txt	Metadata for secondary electron image of the surface of Kanthal APMT before oxidation.
SEM_APMT_Steam.jpg	Secondary electron image of the surface of Kanthal APMT after oxidation in steam.

SEM_APMT_Steam_Metadata.txt	Metadata for secondary electron image of the surface of Kanthal APMT after oxidation in steam.
SEM_T91_Air.jpg	Secondary electron image of the surface of T91 after oxidation in air.
SEM_T91_Air_Metadata.txt	Metadata for secondary electron image of the surface of T91 after oxidation in air.
SEM_T91_Control.jpg	Secondary electron image of the surface of T91 before oxidation.
SEM_T91_Control_Metadata.txt	Metadata for secondary electron image of the surface of T91 before oxidation.
SEM_T91_Steam.jpg	Secondary electron image of the surface of T91 after oxidation in steam.
SEM_T91_Steam_Metadata.txt	Metadata for secondary electron image of the surface of T91 after oxidation in steam.

----- **METHODS AND MATERIALS** -----

----- EQUIPMENT -----

Manufacturer: JEOL

Model: 7600F

Embedded Software/Firmware Name: (if applicable) N/A

Embedded Software/Firmware Version: (if applicable) N/A

Additional Notes: Equipped with Oxford Instruments EDS 80 mm<sup>2</sup> X-Max silicon drift detector (129 eV resolution) operated through the INCA™ software suite.

----- **LICENSING** -----

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